



ThermoFisher
SCIENTIFIC

Signal detection in electron microscopy

Marek Unčovský

Contents

- Introduction
 - What is detector
- Detected signals in electron microscopes
- Technologies used for detection in electron microscopy
- Detector design considerations
- Summary

Detector basics - what is detector?

- Detector is part of imaging system of microscope
- It collects signal radiation in EM, amplifies and converts into form which can be digitized and visualized
- Detectors can be divided into different categories based on:
 - Type of signal they collect
 - Technology they use

Electron beam interaction with sample

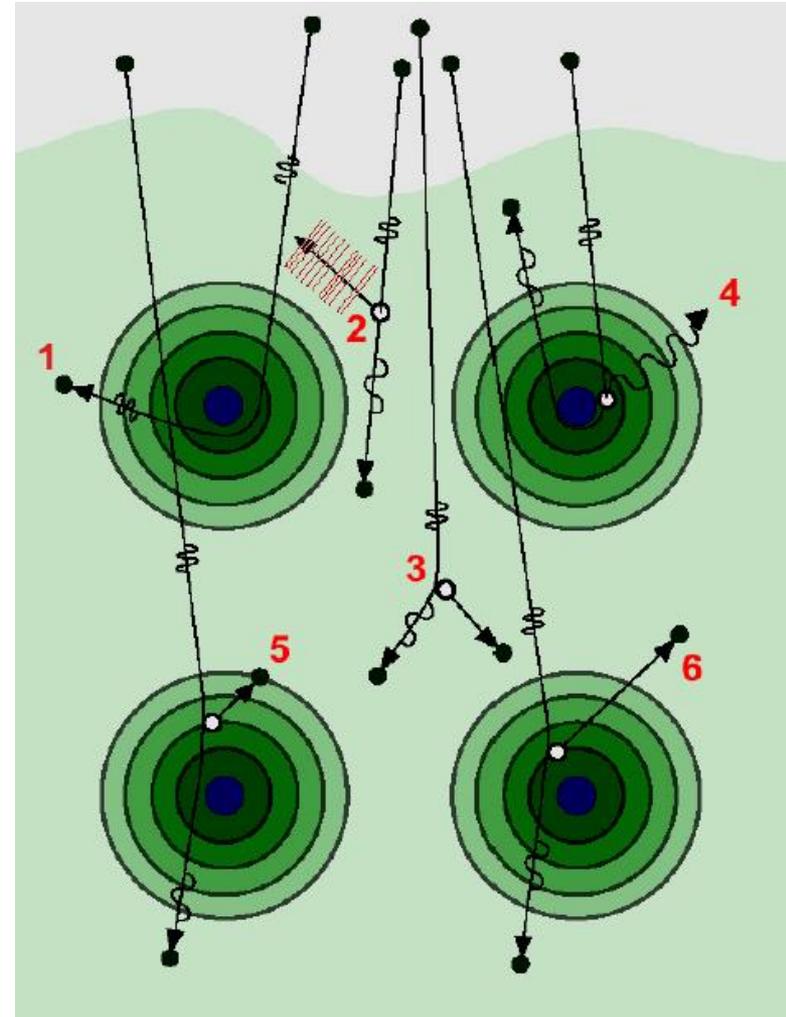
• Scattering processes:

- Elastic

- Rutherford or Mott scattering (1)
-> Low Loss BSE
- Compton scattering (3)

- Inelastic

- Inner/interband transitions (5)
-> SE, AE
- X-ray emission (4)
- phonon and plasmon emission (2)
-> BSE



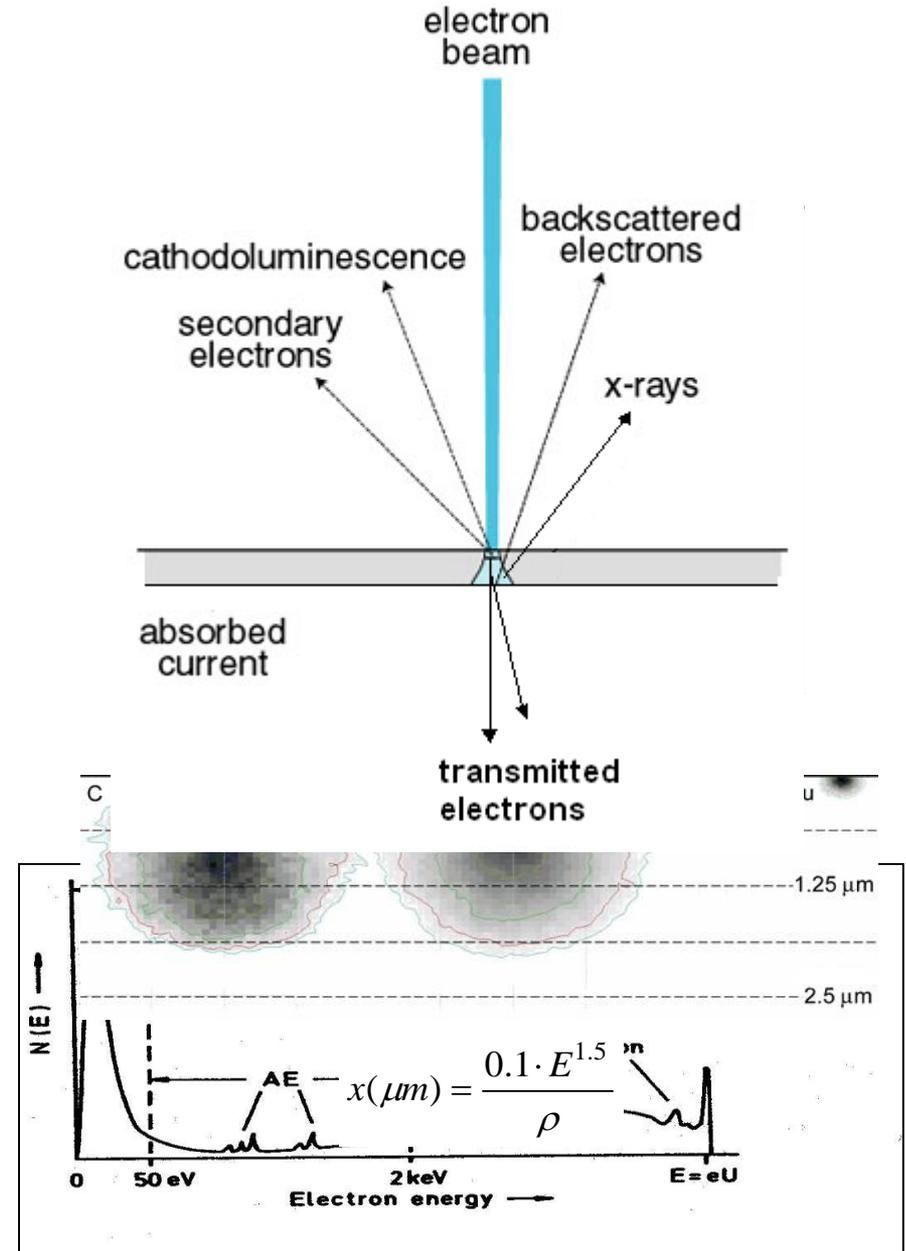
Types of signals detected in electron microscopes

- Electron or ion beam interaction with sample produce various types of particles/radiation = signal
 - Electrons
 - Secondary
 - Backscattered
 - Auger
 - Transmitted
 - Absorbed (specimen current)
 - Photons
 - Cathodoluminescence
 - X-ray
 - Ions
 - Secondary

Electrons

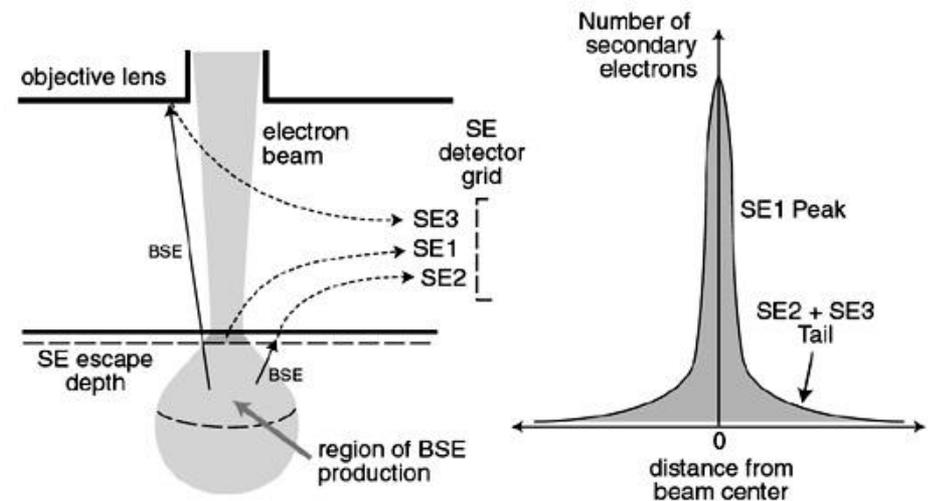
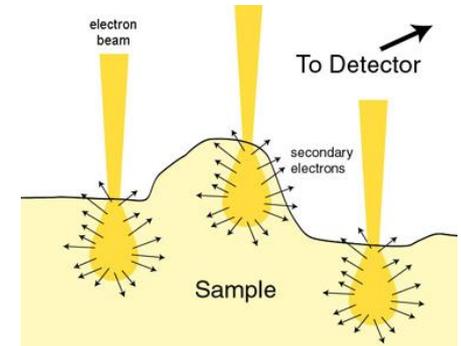
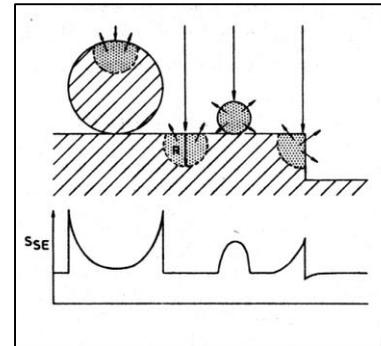
• Electron signals

- Secondary electrons - (SE), $E < 50\text{eV}$, small escape depth ($\sim 10\text{nm}$) \rightarrow best resolution
- Backscattered electrons - (BSE), $50\text{eV} < E \leq E_{\text{primary beam}}$, large interaction volume
- Auger electrons, $E > 50\text{eV}$, characteristic peaks, surface material composition information
- Transmitted electrons (sample must be thin enough)
- Absorbed electrons/current



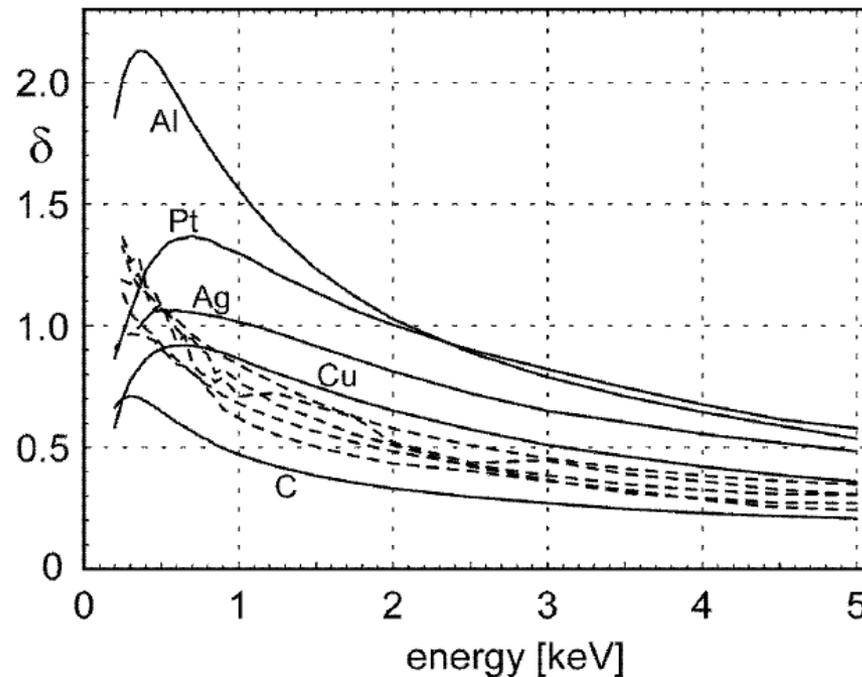
Secondary electrons

- Electrons emitted by the sample under electron beam (inner shell ionization effects)
- Small escape depth \rightarrow high resolution
- Yield depends on local sample tilt \rightarrow Topography contrast
- Yield depends on local magnetic or electrostatic fields
- Signal is polluted by SE created by BSE in sample - SE2, or on some other surface in specimen chamber (usually final lens) - SE3 \rightarrow noise (information from different part of with different contrast)



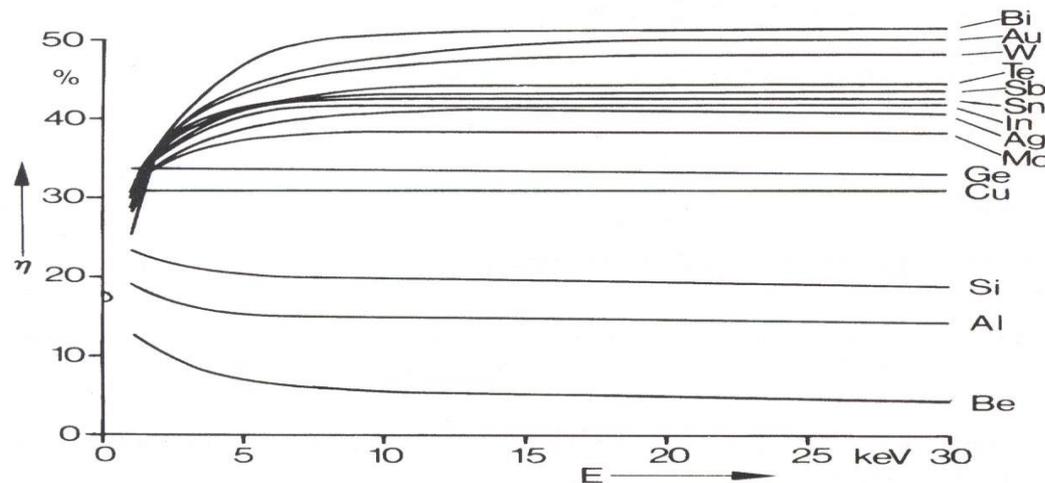
Secondary electrons

- Different yield for different materials \rightarrow material contrast
- Yield changes with primary beam energy \rightarrow for most materials there is equilibrium point where secondary emission balances primary beam current, i.e. no charging occurs even in case that sample is insulator.



Backscattered electrons

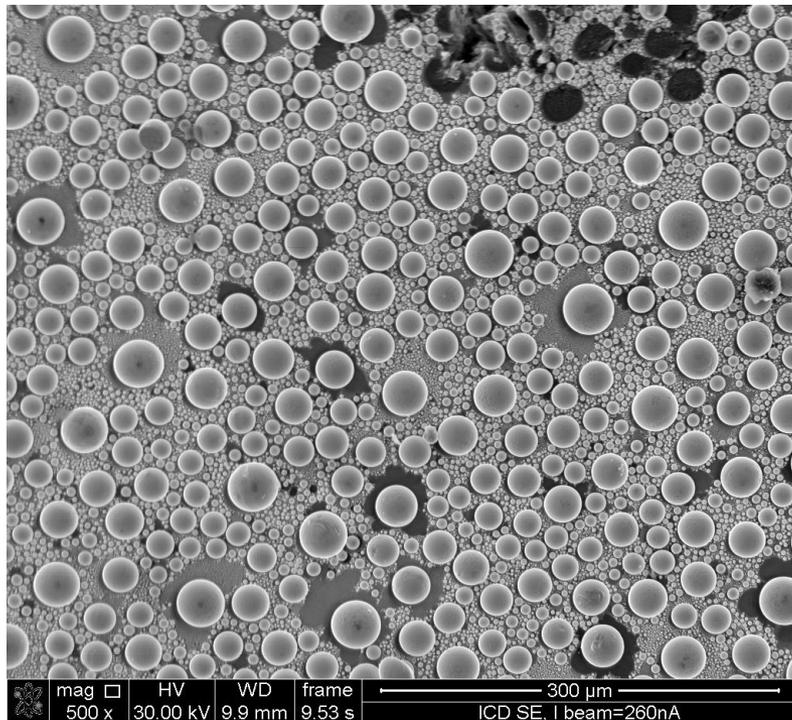
- Primary beam electrons reflected by the sample (elastically or inelastically)
- Yield depends on atomic number of sample material → low loss BSEs reflected close to beam axis - high take off angle
- Yield depends on local tilt of sample surface → BSEs reflected far from beam axis - low take off angles
- Yield depends on crystal orientation → channeling contrast & EBSD(P) = Electron Back Scattered Diffraction (Pattern)



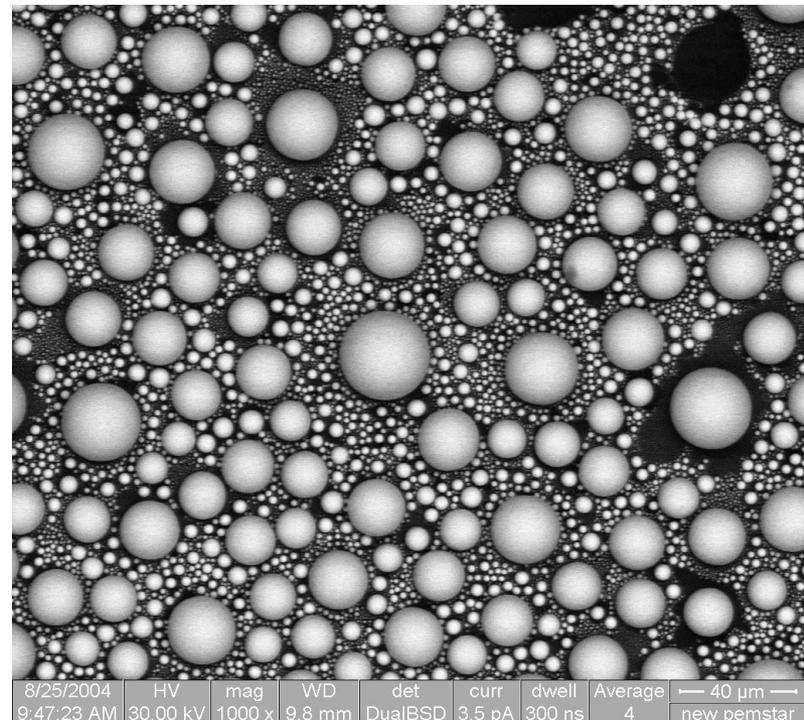
Vybrané partie z elektronové mikroskopie

Examples of SE and BSE images

- SE image

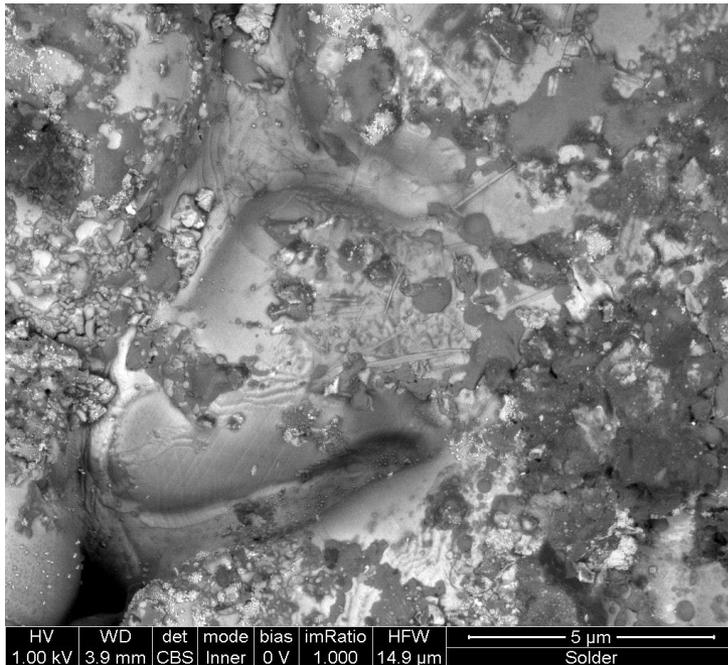


- BSE image

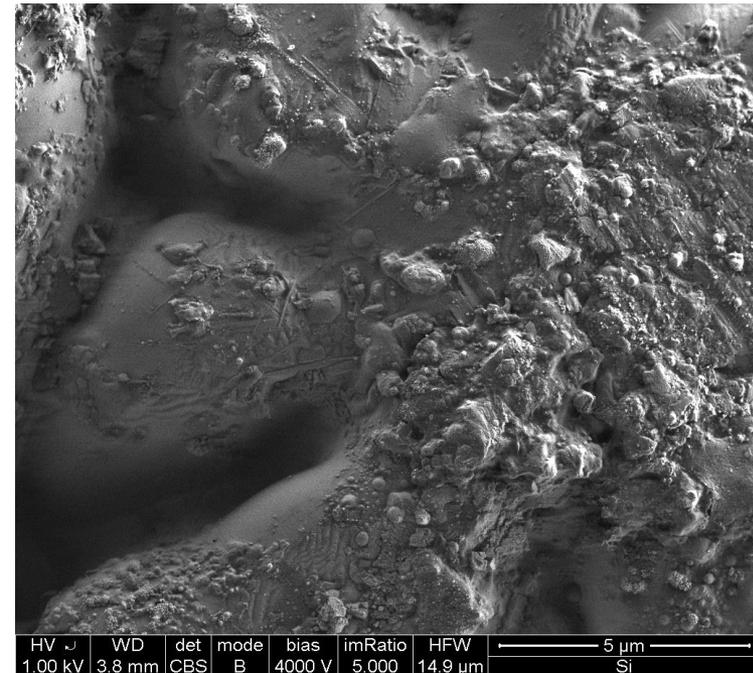


Material & topography contrast in BSE signal

Z- contrast

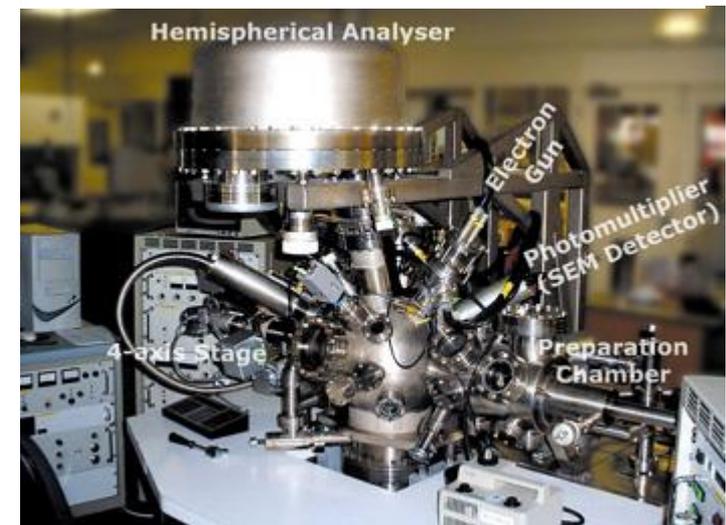
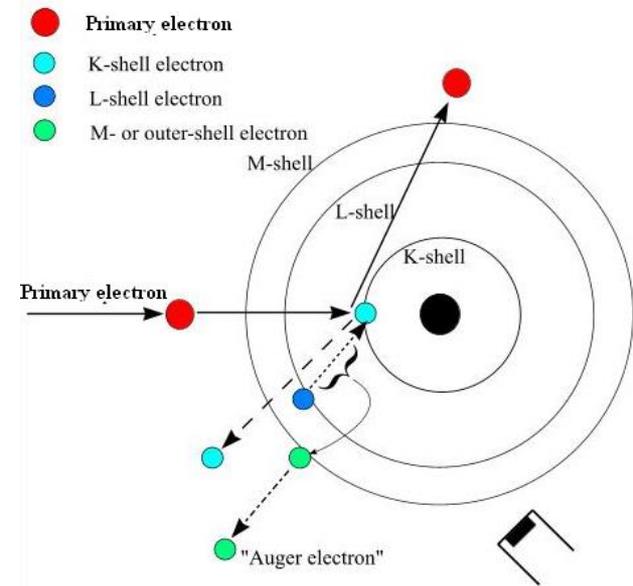


Topography



Auger electrons

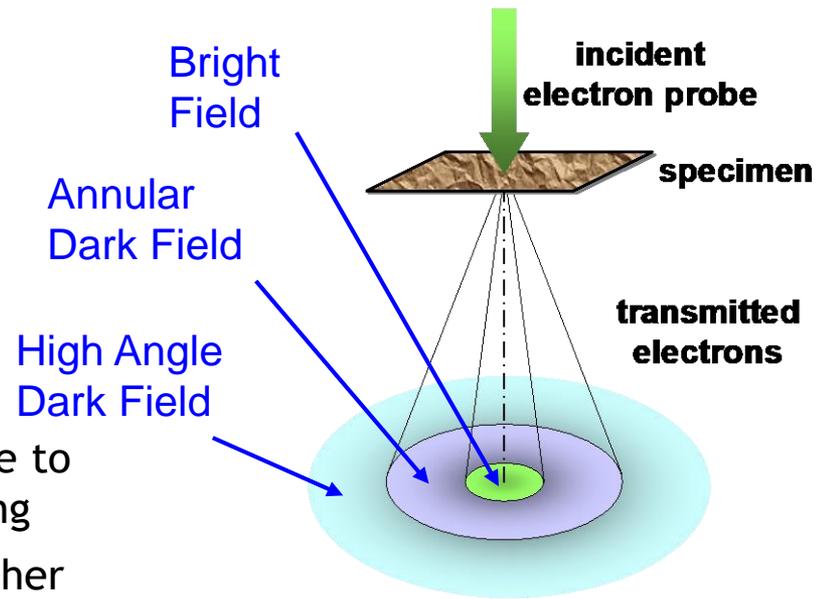
- Transition of electron in atom filling inner shell vacancy results in release of energy
- Energy may be transferred to another electron which is ejected from the atom
- Characteristic peaks for elements - analytical method AES- Auger Electron Spectroscopy
- Low energies (50eV-3keV)-> small escape depth = surface sensitive method
- Extreme surface sensitivity and weakness of signal require usually UHV setup



Transmitted electrons - STEM

(Scanning Transmission Electron Microscopy)

- Electrons transmitted through sample without scattering or scattered to space below sample
- Only possible for samples with thickness smaller than interaction volume
- Signal depends on:
 - Sample thickness
 - Sample material
 - Crystal orientation
- Signals:
 - BF - Bright Field - electrons scattered close to beam axis or transmitted without scattering
 - DF - Dark Field - electrons scattered in higher angle from beam axis
 - HADF - High Angle Dark Field - Higher angle than DF

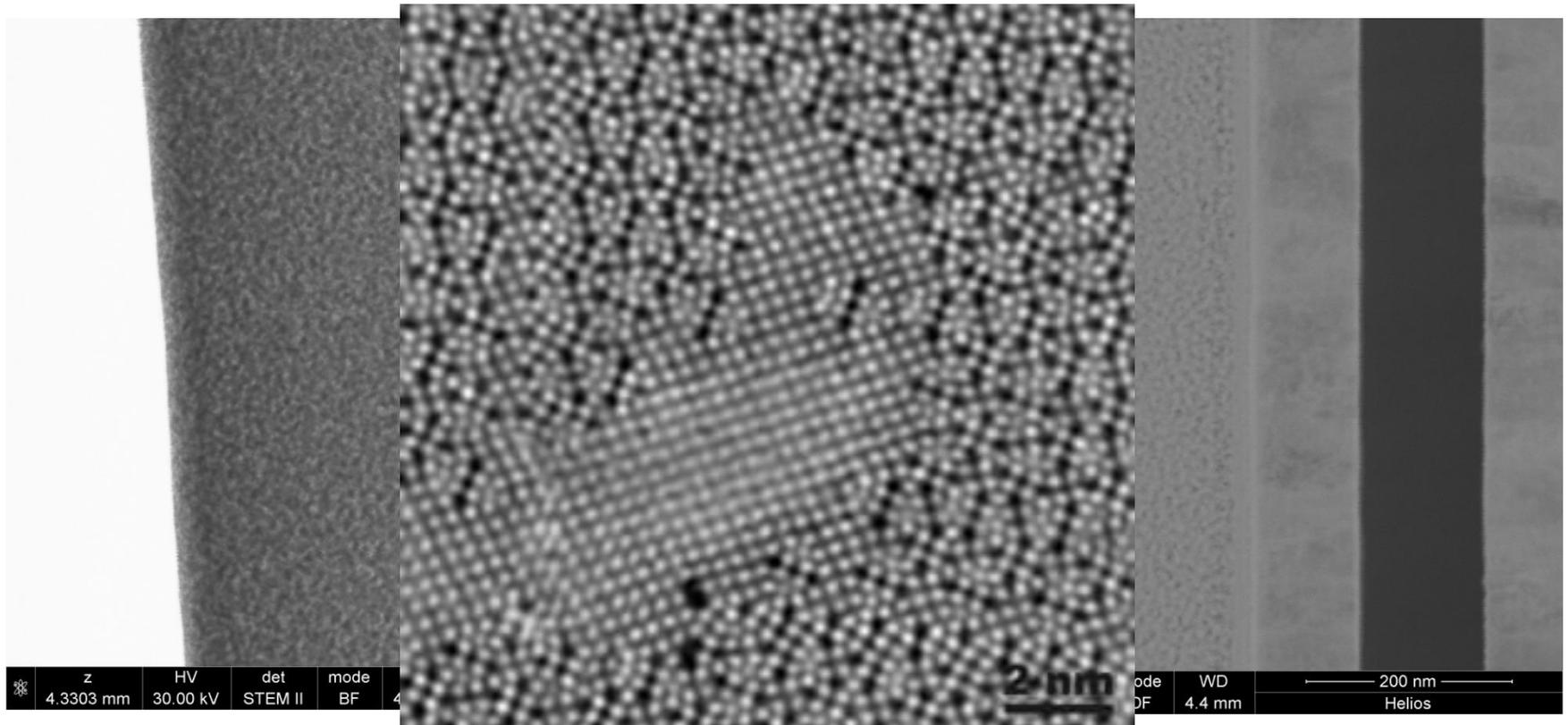


STEM - examples

- Cross section of multilayer (Pt, Mo, Si)

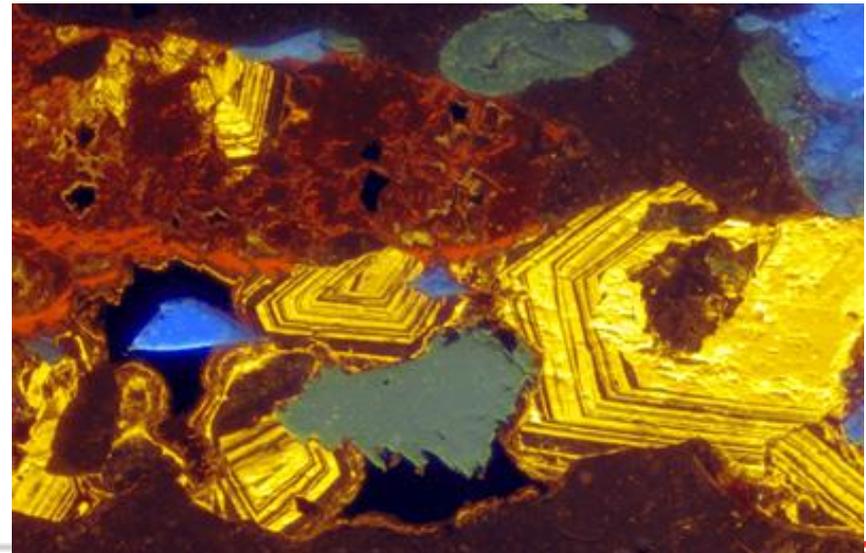
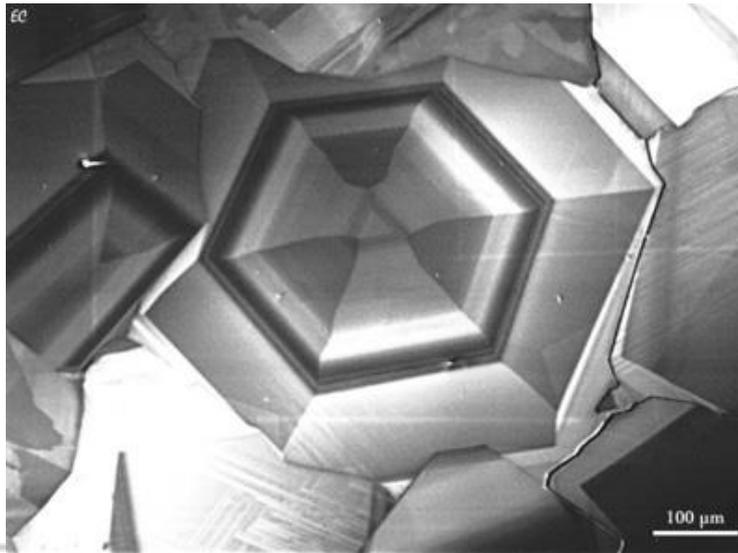
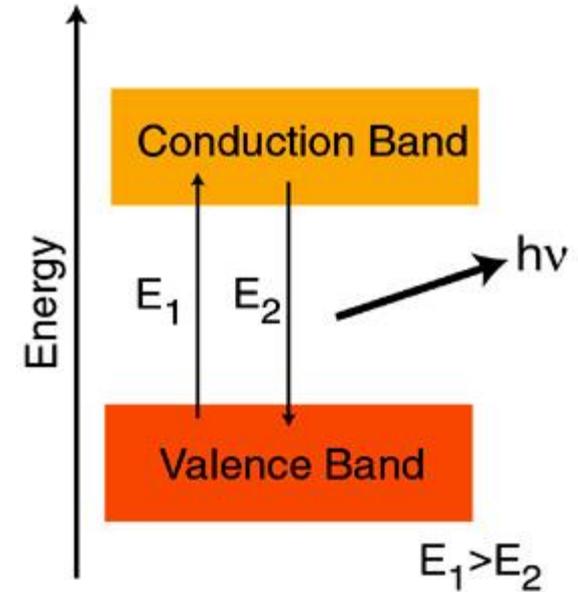
Bright Field

Dark Field



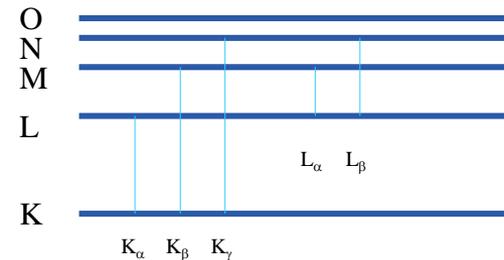
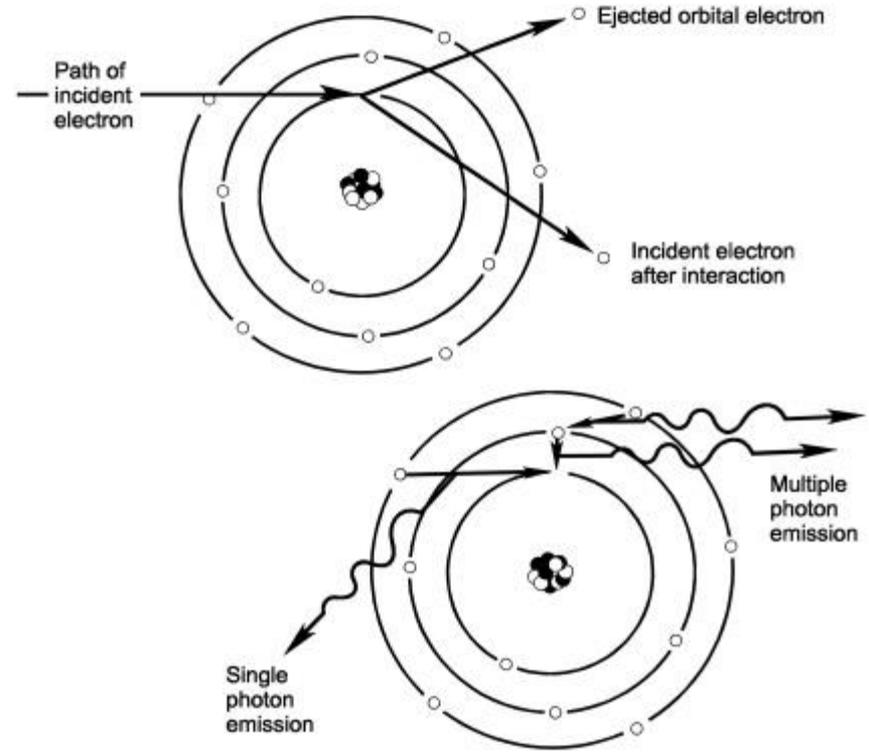
Cathodoluminescence

- UV to IR light (160nm-2000nm) emitted by the sample under electron irradiation
- Effect occurs only in certain materials (semiconductors, minerals, organic molecules)
- Direct detection of light emitted by sample, or more complex instruments with monochromator to obtain spectra of emitted light



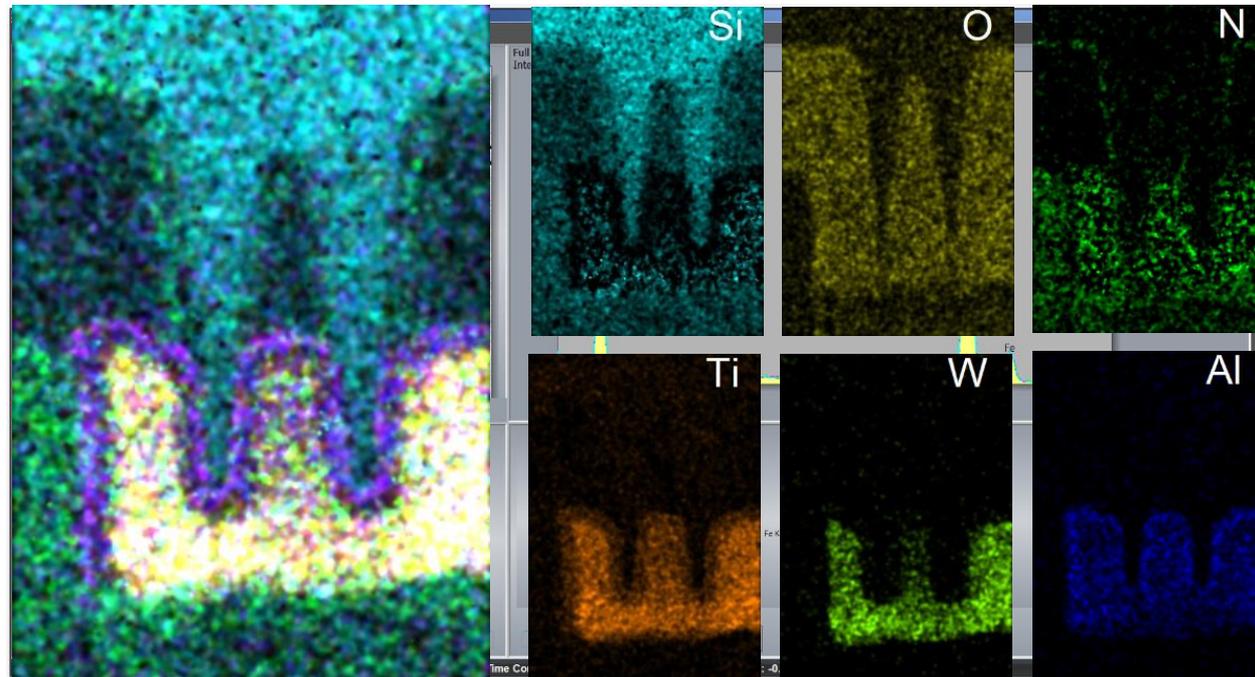
Characteristic X-Ray

- Electron beam induced emission of X-ray has two components
 - Continuous (“brehmstrahlung”)
 - Characteristic X-ray - dependent on atomic structure of sample
- Peaks of characteristic X-ray corresponds to energy emitted by electron when changing energy levels in atom, thus they enable to determine atomic compound of sample (not chemical structure)



Characteristic X-ray

- EDS or WDS (also EDX, WDX)
 - Energy (Wave) Dispersive Spectroscopy (X-ray)
 - EDS - faster x WDS - more accurate (better energy resolution)
 - X-ray spectra
 - X-ray mapping



Other

- Secondary Ions

- Secondary ions are sputtered from sample by ion beam - only in FIB or SDB
- Yield depends on material and crystal orientation
- Can be used for:
 - Imaging (channeling contrast)
 - SIMS - Secondary Ion Mass Spectroscopy - enable to measure atomic compound of sputtered sample

- Specimen current

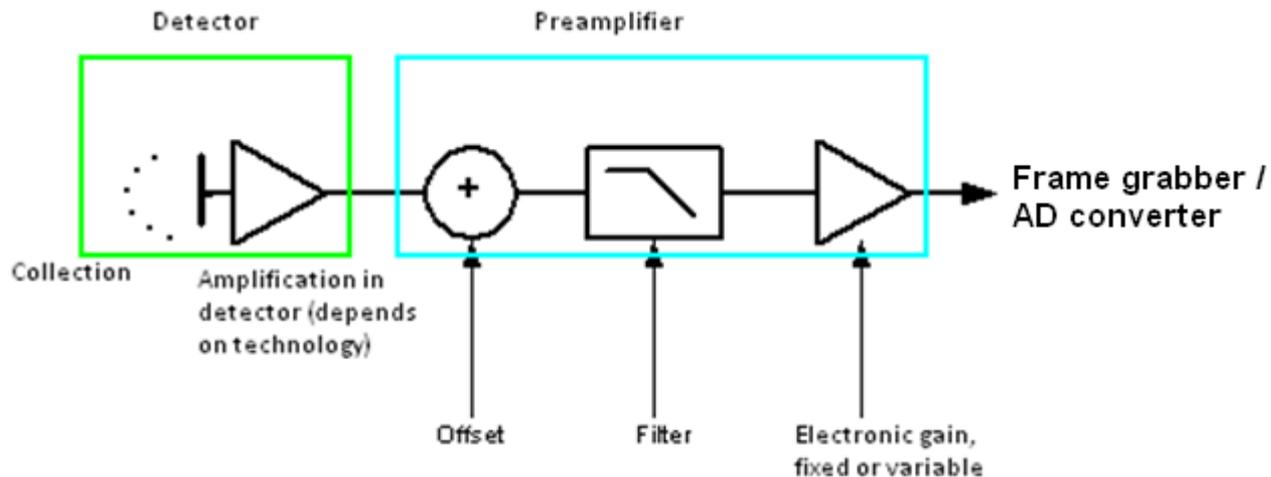
- Signal of absorbed current is complementary to SE+BSE signal
- Usually large currents and long dwell times are needed

Signals in EM - summary

- Topography, shape - Secondary electrons
- Material (qualitatively) - Backscattered electrons,
Cathodoluminescence
STEM
- Material (quantitatively) - Characteristic X-ray,
EELS

Basic Detector Scheme

- Each detector consist of:
 - collection part with primary amplification mechanism depending on technology
 - Preamplifier with additional electronic gain, offset and filtering capabilities which prepares signal for frame grabber

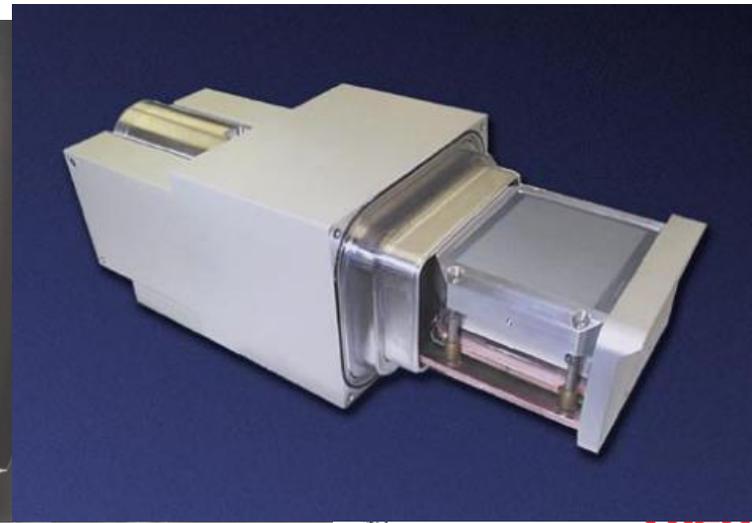


Technologies used for signal detection & amplification

- All detectors used in electron microscopy use several detection principles
 - Scintillation detectors
 - Use materials which emit light when irradiated by electrons
 - Semiconductor detectors
 - Use photodiodes or avalanche diodes with thin entrance window
 - Gaseous ionization detectors
 - Use amplification in gas environment
 - Continuous multipliers
 - Amplification in continuous dynode structure in chamber environment
 - Light detectors
 - For CL detection, uses mirrors and lightguides to get emitted light to PMT
 - Conversion detectors
 - Not special category - detectors which use some structure to convert real signal into different type of signal which can be then detected by some of the above mentioned detector schemes

Scintillation detectors

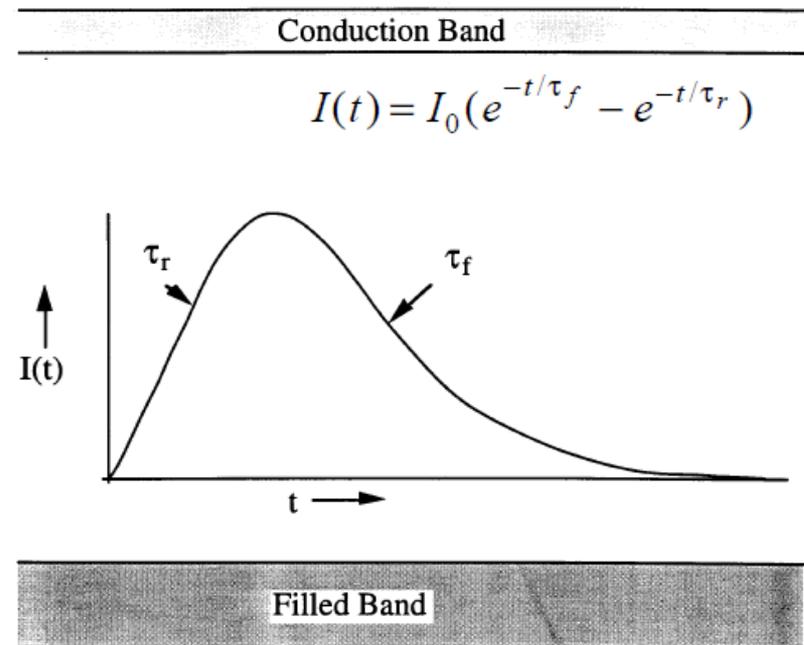
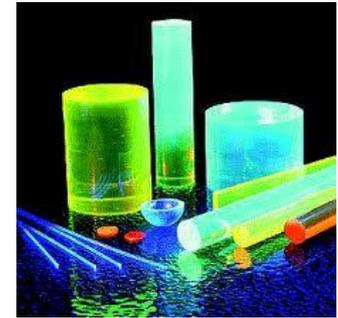
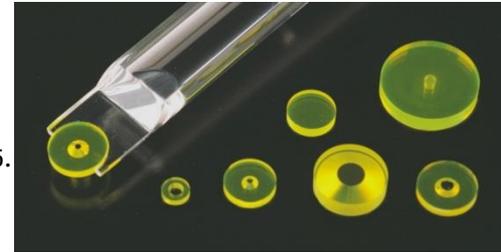
- Signal electrons are converted into light in scintillator
- Light is transported through lightguide to photomultiplier which amplifies signal and converts it to current
- SE detection - scintillator has to be biased so SE's has sufficient energy to scintillate
- BSE detection - No bias needed
- SI (secondary ion) detection - conversion electrode needed to convert ions to SE's, these can be amplified
- TEM phosphor screens/screens of TEM cameras



Components of scintillation detectors

• Scintillator

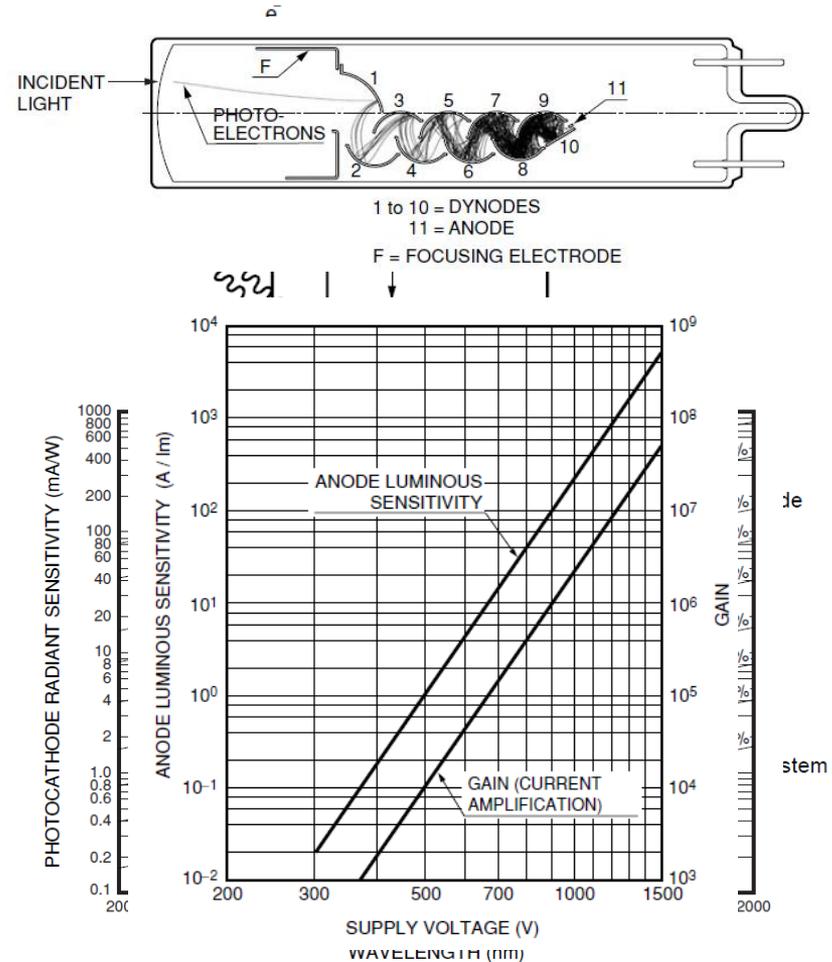
- Single crystal (YAG, YAP..), Powder (P47 = Y_2SiO_5 or organic (PBO..)
- Fluorescence caused by
 - Transition between vibrational states of organic molecules
 - De-excitation of electrons excited in states in forbidden band (inorganic scintillators)
- Basic properties
 - Decay time
 - Light output
 - Emission spectrum
- Electron energy needs to be in range of keV to produce light in scintillator
- Lightguide
 - Has to be matched to scintillator (similar refraction index) and in good optical contact with scintillator and PMT



Components of scintillation detectors

• Photomultiplier (PMT)

- Electron tube with photosensitive cathode - external photoelectric effect
- Photocathode -> external photoelectric effect (Alkali - Sb, Cs, Te, Rb, or III-V semiconductors GaAs...)
- Dynodes (BeO, MgO, GaP...)
- Basic parameters
 - Spectral sensitivity of photocathode
 - Gain $\mu = A \cdot V^{kn}$
 - Linearity
 - Dark current



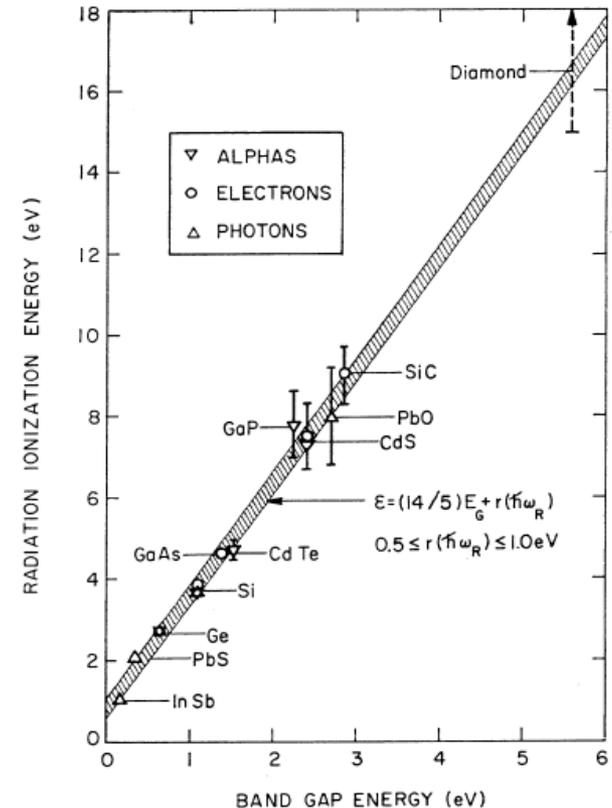
Examples of scintillation detectors

- ETD - Everhardt Thornley detector - standard detector of SEM systems
 - Detector uses biased grid to attract low energy SEs
 - Scintillator is biased to 10kV to provide enough light output
 - In-chamber or in-column versions
- Robinson type BSE detector - Scintillation BSE detector
 - Annular scintillator with central hole for electron beam
- HAADF STEM detector for TEM



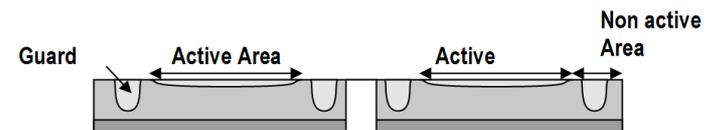
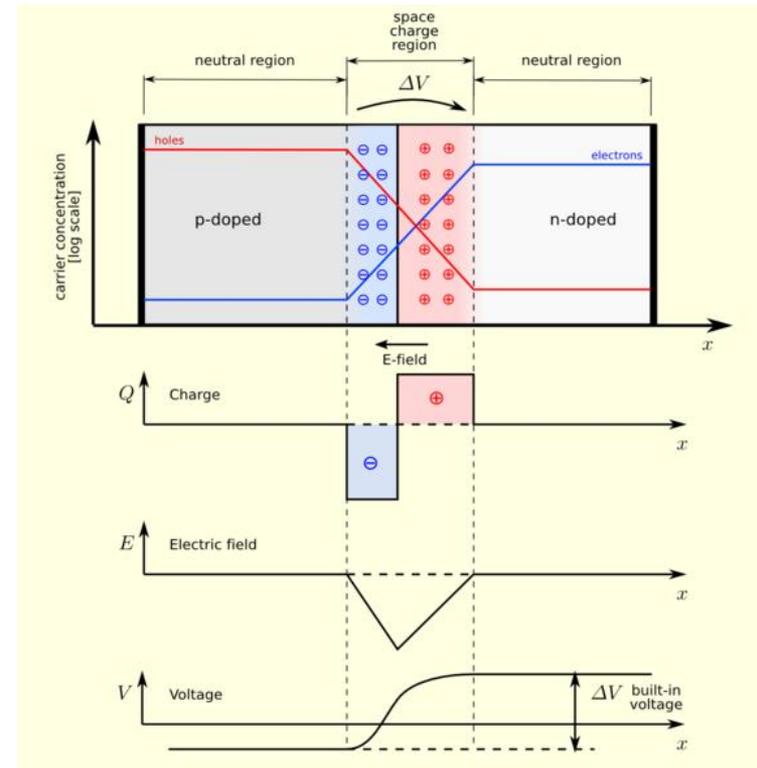
Semiconductor detectors

- Charged particle passing through semiconductor causes production of electron hole pairs
- Ratio $\frac{\varepsilon_i}{E_g} \approx \text{const.}$ for all materials and types of radiation
- Ionization energy $\sim 3\text{eV}$ for both Ge and Si, Fano factor $\sim 0.1 \rightarrow$ good energy resolution
- Several detector types
 - P/N, PIN diodes
 - Avalanche diodes - APDs
 - CCD cameras
 - Direct detectors - CMOS
 - Hybrid pixel detectors
 - X-ray detectors for spectorscopy



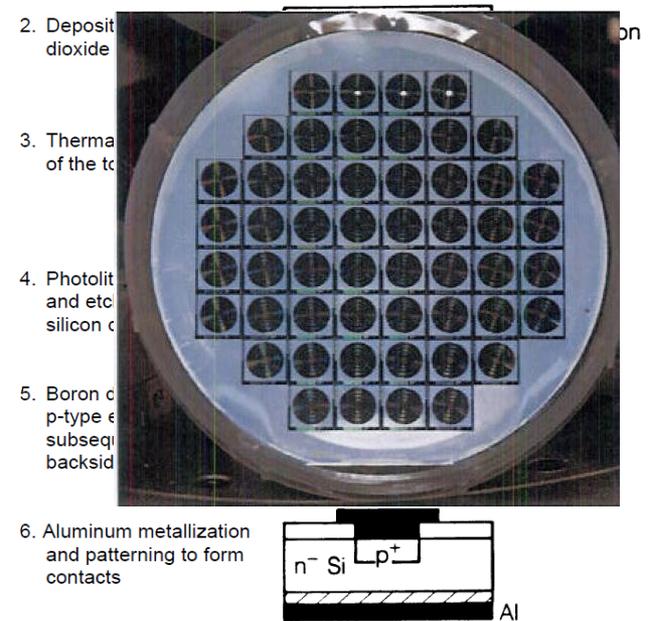
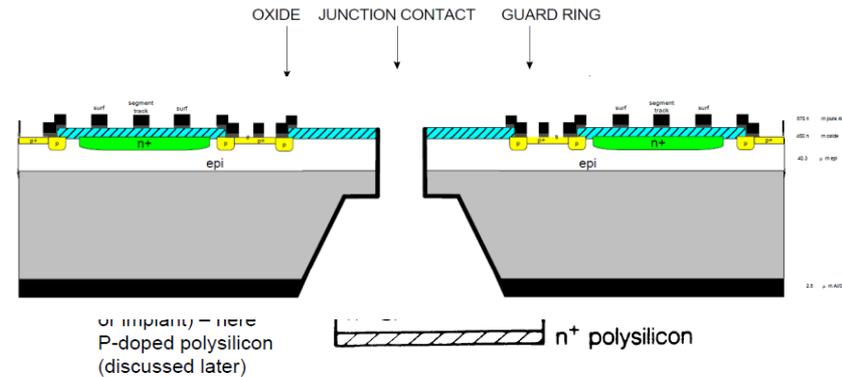
Semiconductor detector - diode

- Equilibrium of drift and diffusion current at p-n junction forms depletion region
- Reverse bias often used to enlarge depletion region (fully depleted detector)
 - Increase active volume
 - Decrease capacitance of the detector
- Shallow implant on the surface needed to not block low energy electrons



Semiconductor detector - diode Fabrication

- Bulk material
 - Semiconductor wafer - Si, Ge, GaAs..
- Dopants to create p and n regions
 - Introduced from the surfaces using diffusion or ion implantation
- Metallization to make contacts
 - Evaporation or sputtering
- Passivation to protect semiconductor surfaces
- Guard ring - additional junction to isolate main junction from detector edge
- Each production step only on selected parts of surface - masks, photoresists

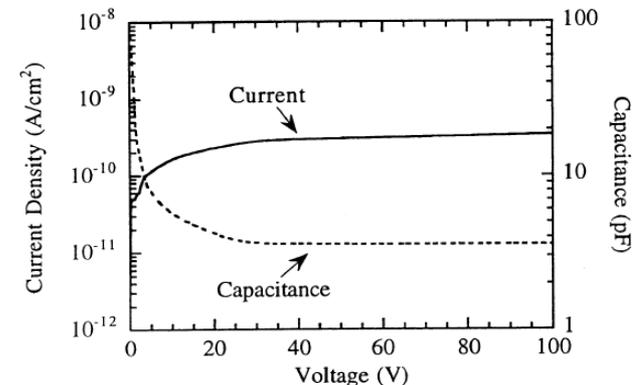
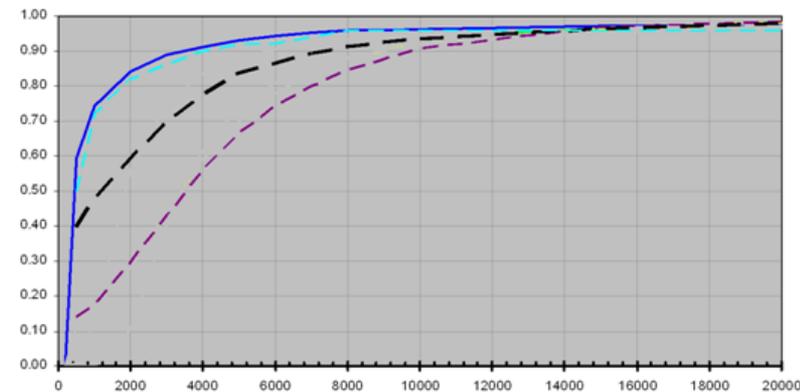


Semiconductor detector - diode

Parameters

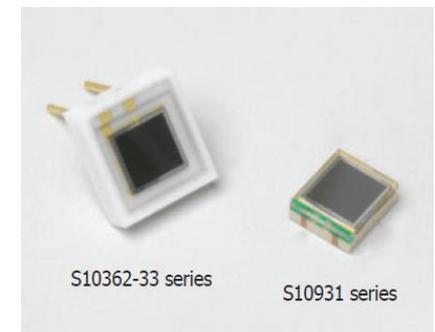
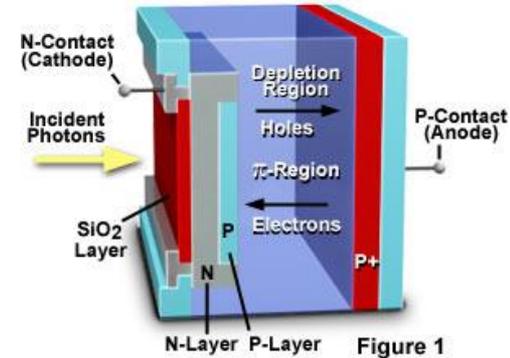
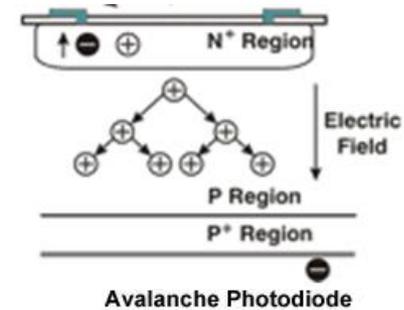
- Energy needed to create one electron - hole pair in silicon is 3.6eV → 30keV electron creates ideally > 8000 electron hole pairs, 1keV electron only ~270
- Thickness of front implant - “dead layer” - low energy electron efficiency
- Capacitance and serial resistance $\tau = RC$ (C = 10pF, R=100Ω → $\tau = 1$ ns)
- Leakage current - Crystal imperfections, temperature, (mechanical damage, surface contamination)

$$I_{\text{det}} = I_{\text{beam}} \cdot \frac{E_{\text{beam}}}{3.62eV} \cdot (1 - \eta) \cdot R$$



Semiconductor (solid state) detectors

- Avalanche photodiodes (APDs)
 - Contrary to PIN diodes charge carriers are accelerated by high bias (up to 2500V)
 - Avalanche electron multiplication in the depletion region similar to process in PMT
 - Higher gain x Higher dark current = noise
 - Recently arrays of APDs are produced which may replace PMT in future (MPPC-multipixel photon counter, SiPM - Silicon photomultiplier)



Semiconductor (solid state) detectors

- Advantages

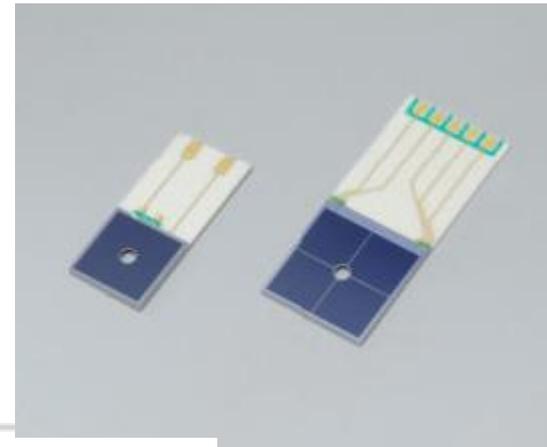
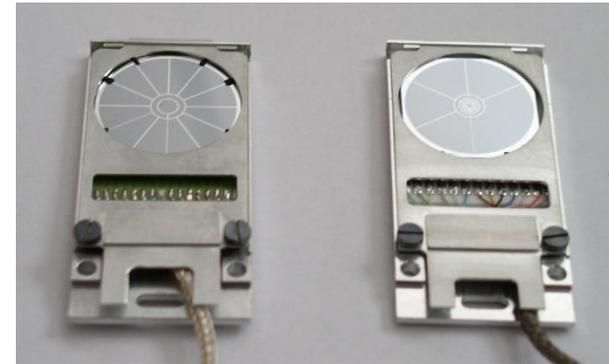
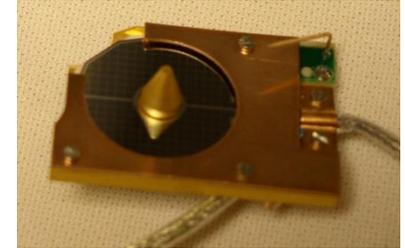
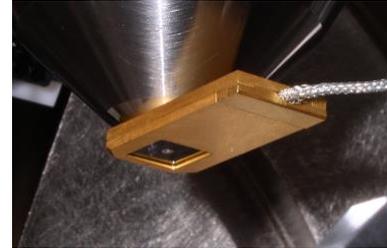
- Segmentation of semiconductor detector is very easy, fabrication of multichannel detectors is easier than with scintillation detectors
- Makes use of progress in silicon industry, not special production like scintillators or PMTs
- Signal is led via cabling in chamber - it does not block excessive spatial angle around the sample

- Disadvantages

- Low keV sensitivity (technology improves)
- Sensitivity to mechanical damage of surface layer
- Relatively higher input cost (masks, production preparation etc.)
- Signal routing in chamber is vulnerable to EMC interference

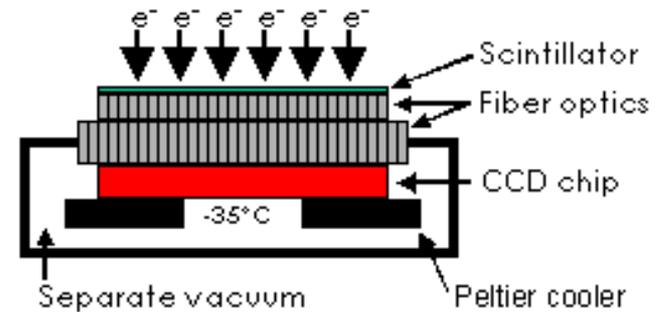
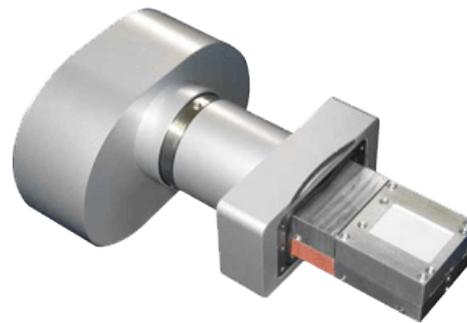
Semiconductor detectors - examples

- Several types of BSE detectors placed below pole piece, different segmentation
- STEM detectors placed below the sample
- In column detectors mounted inside or above objective lens

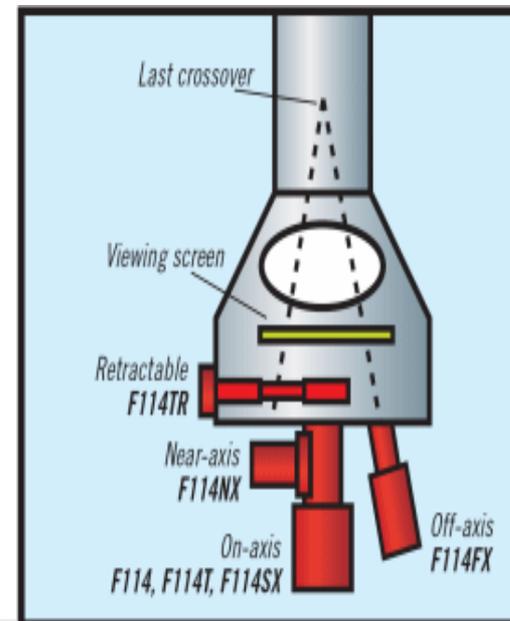


Pixelated detectors CCD camera - TEM

- High resolution CCD cameras
- Fiber optic or lens coupling to scintillator
- Cooling to suppress thermal noise (peltier cooler)
- Variety of different position possibilities



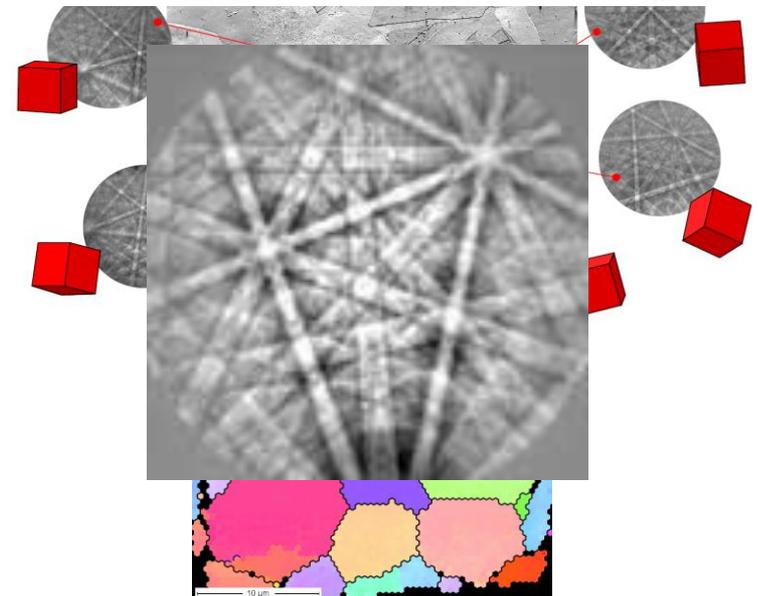
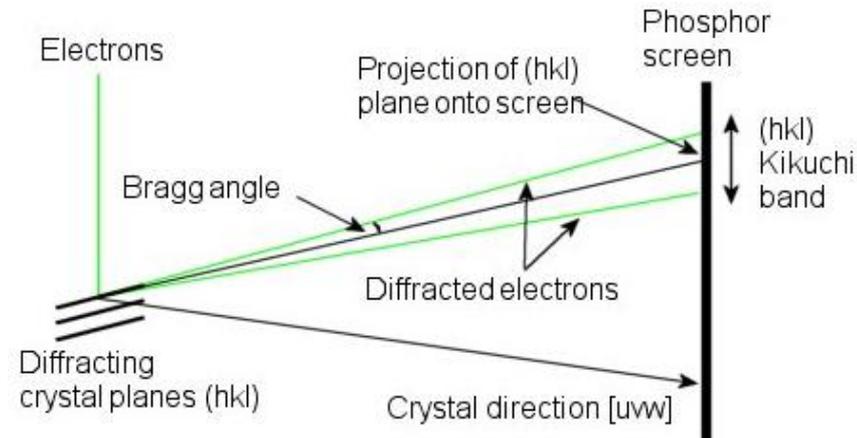
Fiber-optically coupled CCD Camera



Pixelated detectors

CCD camera - EBSD

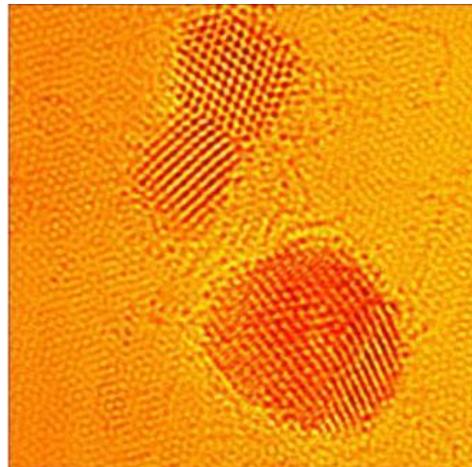
- SEM/SDB uses CCD mostly for EBSD
 - Electron Back Scattered Diffraction Pattern
 - Information about crystal lattice orientation
 - Specimen tilted to 70 degrees
 - EBSD pattern (Kikuchi bands) images taken while scanning
 - Crystal orientation determined for each part of sample (Hough transform)
 - Scintillator coupled to CCD camera



Pixelated detectors

CMOS camera - direct detection - TEM

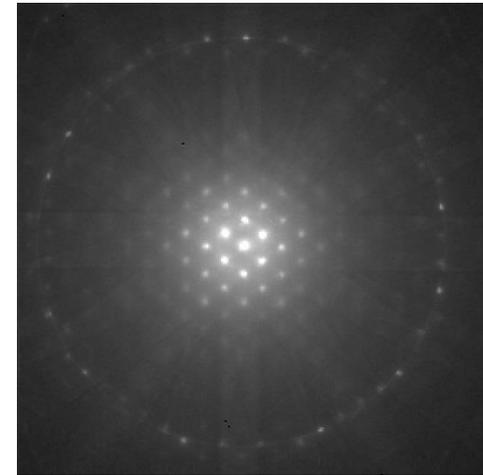
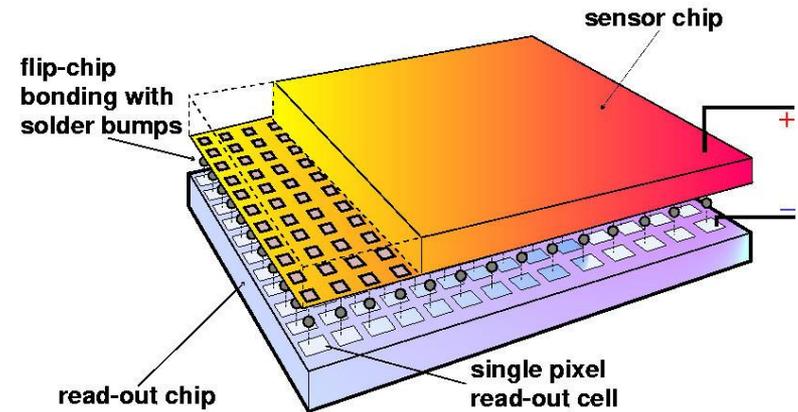
- High resolution / low dose
- Radiation hardness is important
- Pixel sizes $< 5\mu\text{m}$ - comparable to interaction volume
- Interaction volume reduction by backthinning
- Resolution $> 20\text{Mpix}$
- Speeds $> 1000\text{fps}$



Pixelated detectors

Hybrid detectors

- Combination of readout chip (common) and sensor
- Sensors tailor made for application - Si, GaAs, CdTe...
- Higher radiation hardness
- Frame based or data driven mode
- Pixel sizes ~10s of μm



X-ray detectors

- X-ray detectors measure energy of incoming photon by the amount of ionizations it produces in detector material
- Si(Li) and SDD detectors available
- Si(Li) - lithium drifted silicon
 - PIN diode (3-5mm thickness) with ~1000V bias
 - For noise reduction it requires liquid nitrogen cooling
 - External FET transistor to convert current to voltage
 - Resolution ~ 130eV FWHM @ Mn Ka line

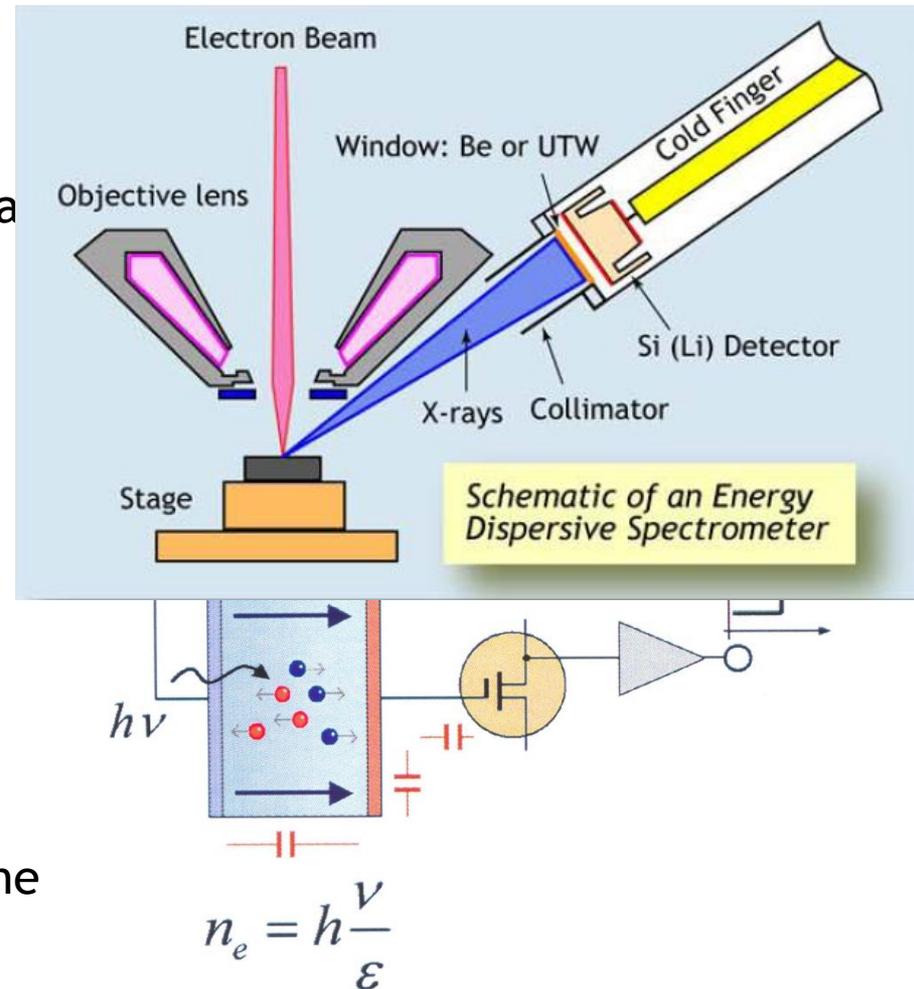


Fig. 8.5-9 Schematic drawing of Si(/Li) detector

X-ray detectors

- SDD detector

- Transversal field generated by serie of ring electrodes causes charge carrier to drift to small collection electrode
- This concept allows significantly higher countrate than Si(Li)
- FET transistor integrated in the chip improves energy resolution and throughput
- High purity allows to use Peltier cooling instead of liquid nitrogen
- Resolution ~ 130eV FWHM @ Mn Ka line
- Countrate up to 1,000,000 cps, better energy resolution at given countrate

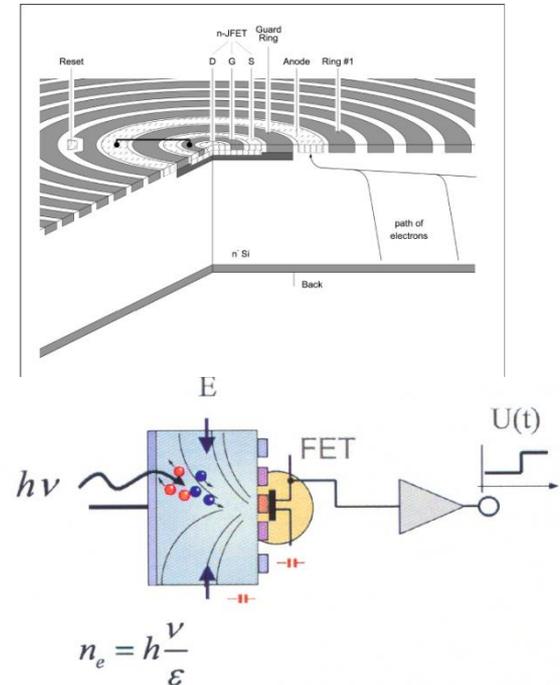


Fig. 8.5-10 Schematic drawing of SDD detector

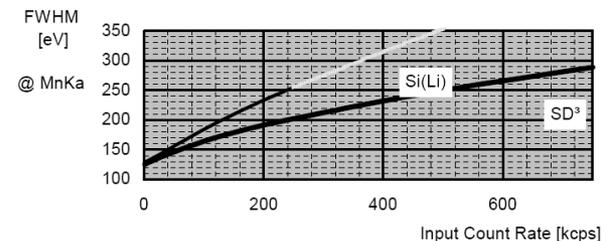
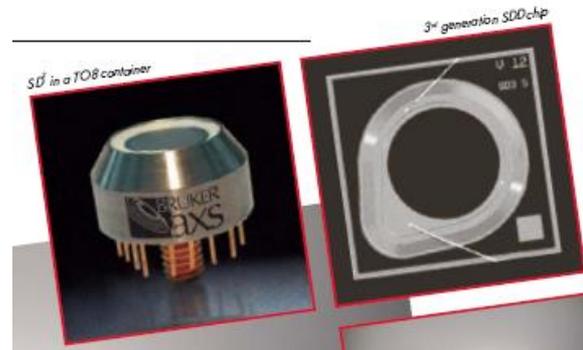


Fig. 1. Energy Resolution (FWHM) of SD³ Detectors and state-of-the-art Si(Li)

X-ray detectors - examples

- SDD chip



- Si(Li) detector



- SDD detector



Gaseous ionization detectors

- Low Vacuum or ESEM (Environmental Scanning Electron Microscopy) mode is used for imaging of non conductive samples
- Chamber pressure vary between 10-4000 Pa -> biased scintillation detectors cannot be used
- Amplification in chamber gas environment - biased electrode (~0-800V)

• Maximum bias given by Paschen law $V = \frac{a \cdot p \cdot d}{\ln(p \cdot d) + b}$

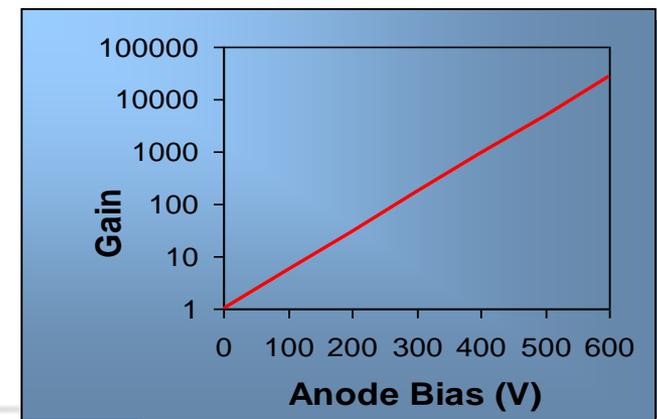
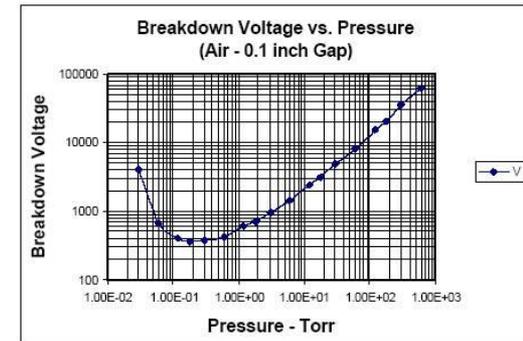
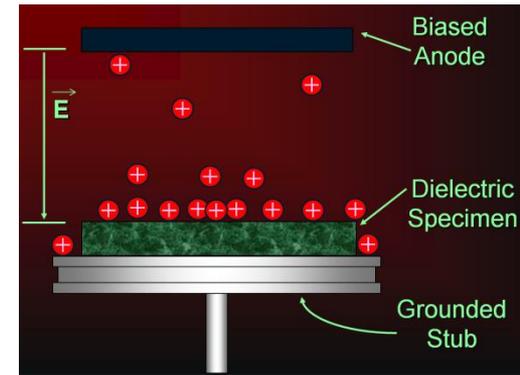
• Gain is determined by gap distance, gas type, pressure and anode bias

$$g = e^{\alpha d}$$

$$\alpha = AP e^{-BPd/V_0}$$

• Optimum exists in gain dependence on Pd/V_0

Inelastic mean free path ~ length needed to achieve ionization energy



Gaseous ionization detectors

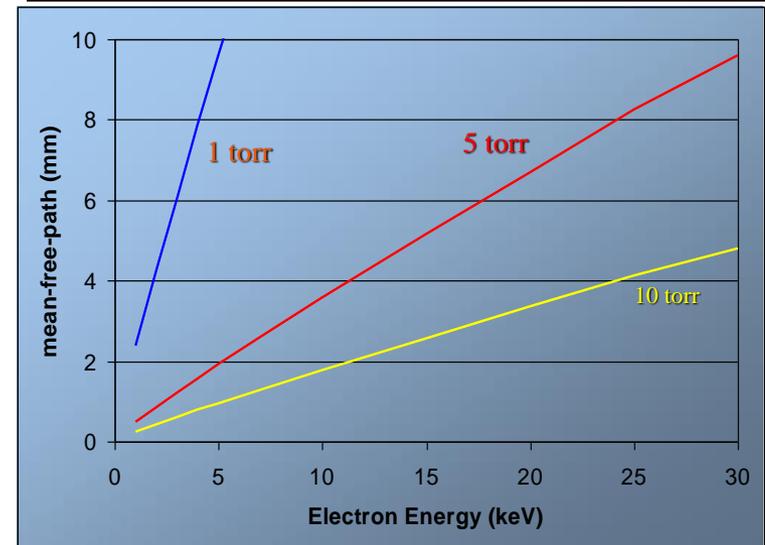
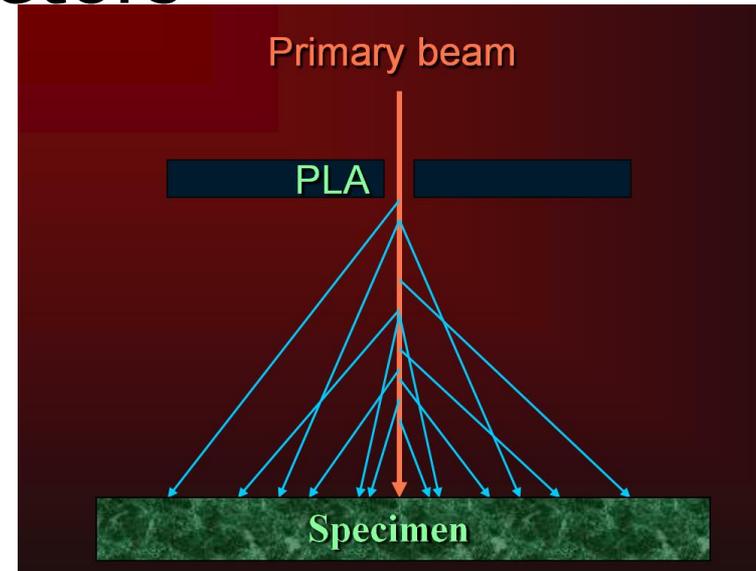
- Additional effects influencing/limiting signal of gaseous detectors

- BSE signal amplification
- Primary beam amplification

$$I = I_0 e^{\alpha d} \left(\delta + \frac{S_{PE}}{\alpha d} + \eta \frac{S_{BSE}}{\alpha d} \right)$$

- Skirt effect - elastic scattering of primary beam

$$r_s = \frac{364 \cdot Z}{E} \left(\frac{p}{T} \right)^{1/2} L^{3/2}$$



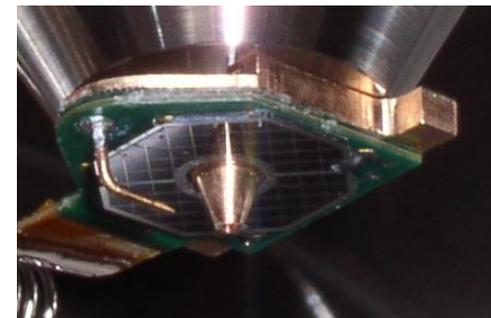
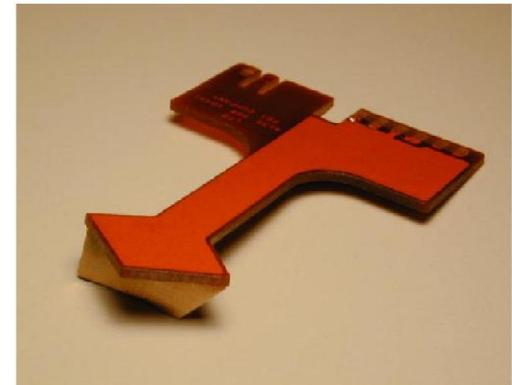
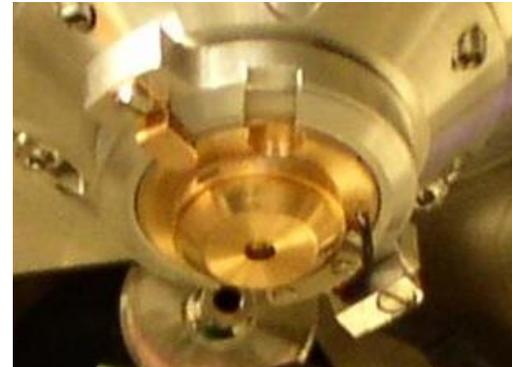
Gaseous ionization detectors

- Advantages

- Cheap production, no special know how needed (PCB, metal electrodes)
- Can be tailor made for given application
- Robust and user exchangeable

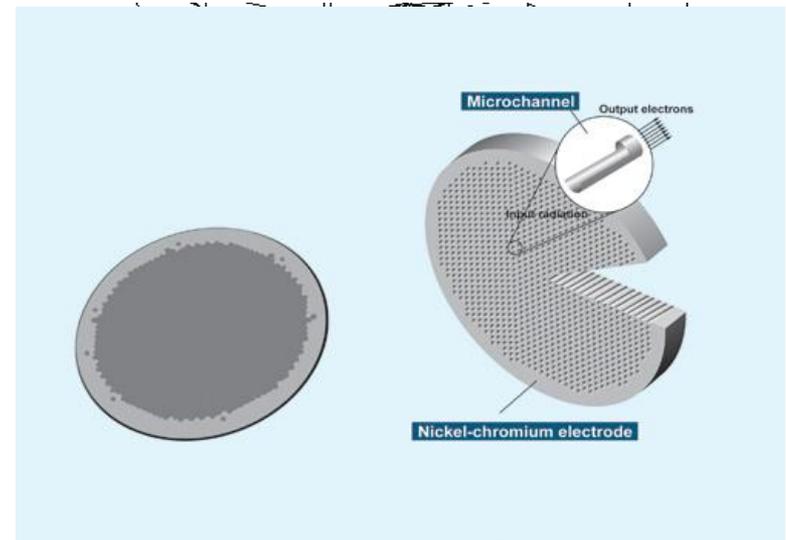
- Disadvantages

- ESEM versions of detectors (with PLA) limit field of view significantly
- Slower response time due to current induced by slow ions produced in amplification cascade
- Needs biased amplifier which complicates multichannel detector schemes



Continuous multipliers

- Structures created from material with high secondary emission yield (or covered with layer with this feature)
- Electric field is distributed along the channel of multiplier placed directly in SEM/SDB chamber
- Signal particle creates SE in input part of detector and this is further amplified similarly to PMT
- More channels can be combined in microchannel plate → position sensitive detectors



Continuous multipliers

- Advantages

- Small size w.r.t. PMT detectors x similar gain
- Can be used to detect both electrons and ions

- Disadvantages

- Sensitive layer providing amplification degrades with time and use, detectors need to be exchanged after some time, when used heavily it could be a few months
- Biased preamplifier needed for this type of detectors

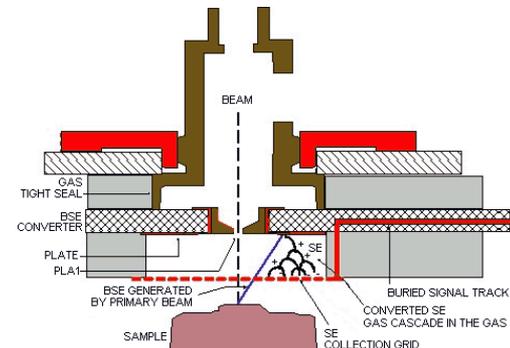
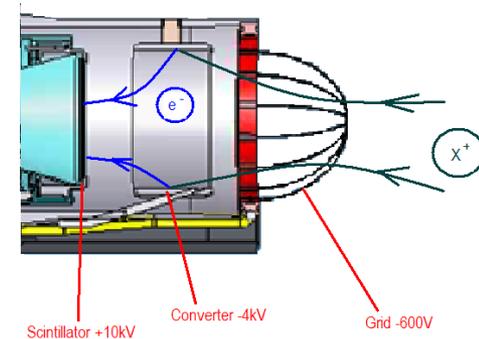
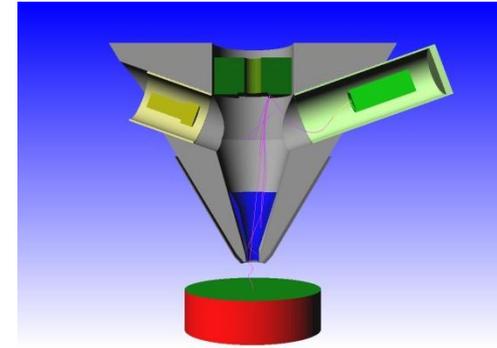
Cathodoluminescence detectors

- Uses mirrors to transport light generated by electron beam on the sample to light sensor
- Examples
 - Centaurus CL - version of BSE detector with exchangeable tip - instead of scintillator only mirror placed above sample the rest of detector remains the same - simple CL detector
 - Gatan Chroma CL - Detector with monochromator enabling to determine also spectrum of emitted light



Conversion Detectors

- BSE mode of TLD
 - BSEs converted on mirror electrode to SEs, then detected
- SI mode of ICE
 - Secondary ions converted on conversion ring to SE's, then detected
- BSE mode of GBSD
 - BSE's converted on inner electrode of detector to SE's , then detected



Technologies used for signal detection

Summary

- Scintillation
 - Coupling to PMT or other light sensitive devices
 - SE, BSE detection
 - Fast, low noise
- Solid state - semiconductor
 - Variety of use cases, BSE, EBSD, EDS...
 - Direct detection, multichannel detection
 - Benefits from progress in semiconductor industry
- Gas ionization
 - Low Vac, ESEM, charge neutralization
- Other technologies
 - Continuous multipliers
 - Cathodoluminescence

Detector design considerations

- Collection efficiency

$$SNR \sim \sqrt{N}$$

- Simulation tools enable modeling of collection efficiency of different detector configurations including beam sample interaction

- Narrow point spread function

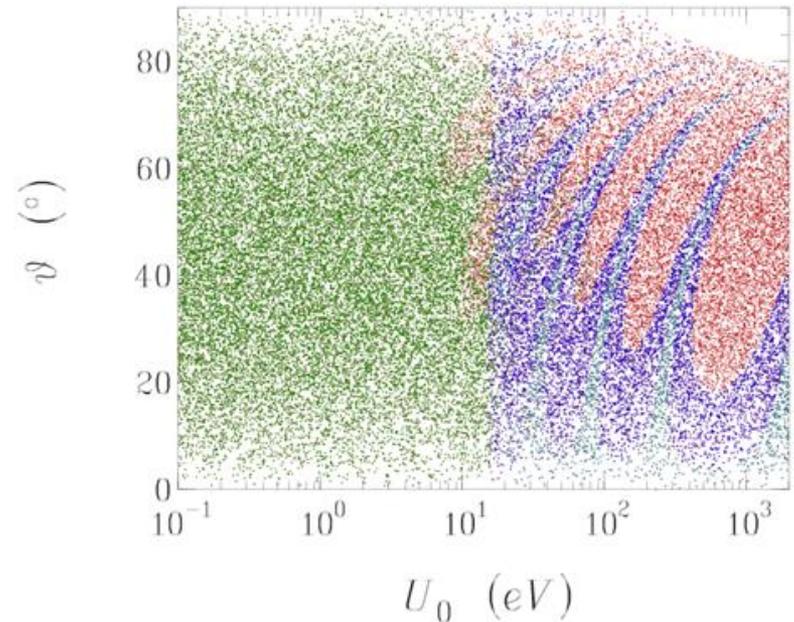
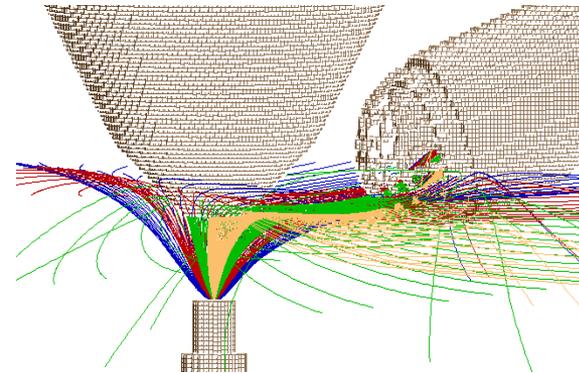
- Scintillator decay time, semiconductor sensor capacitance

- Low additional noise

- Low losses in signal transport (scintillator photocathode matching, lightguide transport efficiency, signal wiring capacitance)

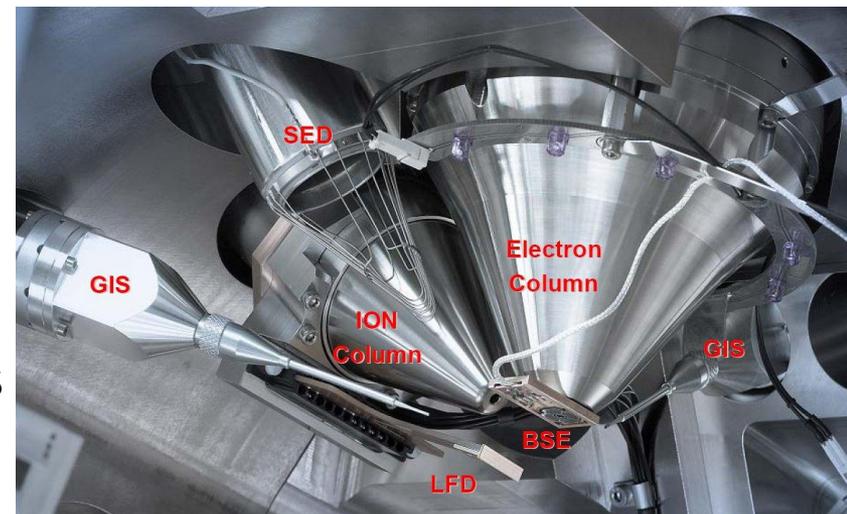
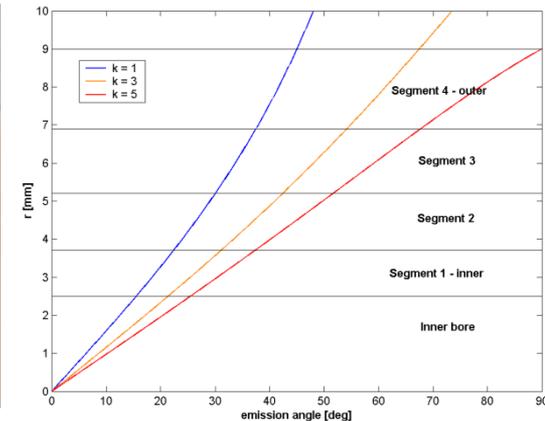
$$DQE = \frac{SNR_{out}^2}{SNR_{in}^2}$$

- Noise free amplification, reduced electronic noise



Detector design considerations

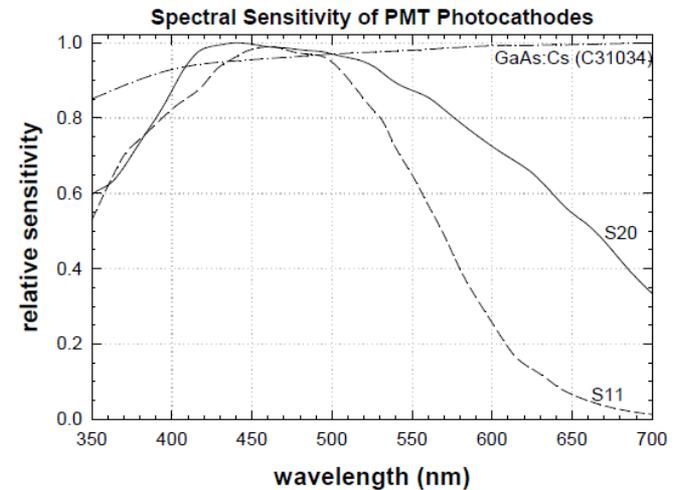
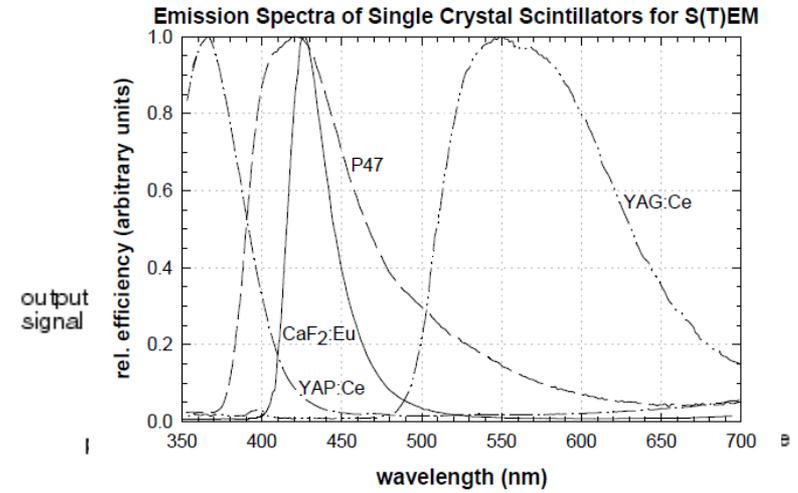
- Possibility of signal filtering
 - Spatial (angular distribution)
 - Energy
- Simultaneous acquisition
 - Variety of signals at the same time
 - Multichannel detection, acquisition and processing
- Spatial requirements
 - Space around the sample is limited
 - Number of SEM/SDB/TEM accessories is increasing



Detector design example

- ETD

- Collection efficiency ~30%
- P47 scintillator 1 signal electron ~100 photons - decay time ~80ns
- Losses in scintillator, lightguide and interfaces ~20-30 photons reaching photocathode
- According to cathode DQE (30-50%) ~10 photoelectrons produced
- Amplification in PMT => 10^6 electrons at PMT anode



Summary

- Detectors are key part of the electron microscope - eyes of the system
- Detect signals produced by interaction of electron or ion beam with sample
 - Electrons (secondary, backscattered, Auger...)
 - Photons (X-Ray, Cathodoluminescence)
 - Ions
- Use different technologies to convert and amplify particle signal into current/voltage which can be digitized and visualized
 - Scintillators
 - Semiconductors
 - Gas amplification

Literature

- Knoll, G. F.: Radiation detection and measurement, ISBN 0-471-07338-5
- Spieler, H.: Introduction to radiation detectors, http://www-physics.lbl.gov/~spieler/physics_198_notes_1999/
- Reimer L.: Scanning Electron Microscopy - Physics of Image Formation and Microanalysis, ISBN: 3-540-63976-4
- Hamamatsu photonics K.K.: Photomultiplier Tubes - Basics and Applications
http://sales.hamamatsu.com/assets/applications/ETD/pmt_handbook_complete.pdf